

Amendments to the Specification:

Please replace the paragraph beginning at page 25, line 22 with the following amended paragraph:

Reference numeral 606 indicates a coil shape electrode (antenna) and 609 indicates a quartz substrate plate. Dielectric magnetic field is generated by supplying electric power from RF power source 605 to an electrode 606 and is applied into the chamber through the quartz substrate plate. Electrons are accelerated and plasma is generated according to the dielectric magnetic field.

Please replace the paragraph beginning at page 26, line 6 with the following amended paragraph:

The quartz substrate plate 609 is exposed to the inside of the chamber in the ICP etching apparatus shown in FIG. 6. And BO_x is attached to the surface exposed to the inside of the chamber when BCl_3 or the like is used as an etching gas. According to the cleaning method of the present invention, the BO_x attached to the quartz substrate plate can be removed and decline in plasma density inside the chamber due to the BO_x can be suppressed.